Notice of References Cited

Application/Control No.

O9/847,511

Examiner

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Applicant(s)/Patent Under
Reexamination
WANG ET AL.

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U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	Α	US-4,417,945	11-1983	Komatsuzaki, Yasuo	438/747
	В	US-5,593,505	01-1997	Erk et al.	134/1.3
	С	US-5,992,431	11-1999	Weber et al.	134/135
	D	US-5,988,186	11-1999	Ward et al.	134/1.3
	Е	US-5,003,999	04-1991	Cardani et al.	134/105
	F	US-4,657,631	04-1987	Noguchi, Hiromichi	216/27
	G	US-5,816,274	10-1998	Bartram et al.	134/140
	Н	US-4,902,350	02-1990	Steck, Ricky B.	134/1
	ı	US-5,839,460	11-1998	Chai et al.	134/147
	J	US-5,626,159	05-1997	Erk et al.	134/147
	к	US-6,257,255	07-2001	Oshinowo, John	134/141
	L	US-6,240,938	06-2001	Oshinowo, John	134/147
	М	US-5,279,991	01-1994	Minahan et al.	438/109

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	0					
	Р					
	Q					
	R					
	S					
	Т					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Handbook of Semiconductor Wafer Cleaning Technology edited by W.Kern. Noyes Publications, 1993, page 24.
	v	
	W	
	х	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).) Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.